

Docket No. 740756-2708
Application No. 10/772,267
Page 12

REMARKS

The above amendment with the following remarks is submitted to be fully responsive to the Office Action of April 9, 2007. Reconsideration of this application in light of the amendment and the allowance of this application are respectfully requested.

Claims 1, 3-4, 9-12, 19-23, 29-31 and 33-45 were pending in the present application prior to the above amendment. In response to the Office Action, claims 1, 9, and 19 are amended and claims 46-60 are added. No new matter is added by these new claims. Therefore, claims 1, 3-4, 9-12, 19-23, 29-31 and 33-60 are now pending in the present application and are believed to be in proper condition for allowance.

Referring now to the Office Action, claims 1, 3-4, 29-30 and 41 are rejected under 35 U.S.C. 103(a) as being unpatentable over U.S. Patent No. 5,679,167 to Muehlberger in view of U.S. Patent No. 6,203,619 to McMillan and U.S. Patent No. 5,563,095 to Frey. Further, claims 9-12, 19-23, 31 and 33-40 are rejected under 35 U.S.C. 103(a) as being unpatentable over U.S. Patent No. 5,679,167 to Muehlberger in view of U.S. Patent No. 6,203,619 to McMillan and U.S. Patent No. 5,563,095 to Frey and U.S. Patent 6,871,943 to Ogawa.

In the Office Action, the Examiner states that "Muehlberger discloses a semiconductor manufacturing apparatus" comprising "at least one plasma generating means for performing a plasma treatment/at least one droplet spraying means for spraying a droplet to the object to be processed (column 7, rows 17-21)".

Applicant submits that, in the Muehlberger reference, the plasma system 10 includes a powder source 26 for providing material to be sprayed to the inside of the plasma gun 14, as described in column 7, lines 17-19. The powder particles entering the chamber 40 from the passages 42 and 44 are entrained into the plasma stream 20 where they mix with the gas of the plasma stream 20, as described in column 8, lines 7-10. In this manner, the plasma gun 14 outputs the plasma stream 20 together with the powder in the Muehlberger reference. Even if the powder is sprayed at this time, the plasma means and the spray means are provided in one chamber 12 of FIG. 1 of the Muehlberger reference.

Contrary to this, in the present invention as claimed in independent claims 1, 9 and 19, as amended, a plasma generating device is provided in a first chamber and an ink-jet device is provided in a second chamber. Thus, the Muehlberger reference does not teach each and every feature of the present invention as claimed in amended independent claims 1, 9 and 19.

Docket No. 740756-2708
Application No. 10/772,267
Page 13

The McMillan, Frey, and Ogawa references do not remedy the deficiencies of the Muehlberger reference.

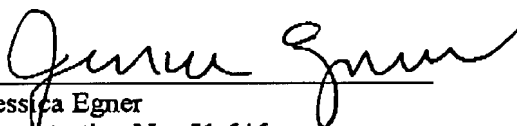
Because neither Muehlberger, McMillan, Frey, nor Ogawa teaches or describe a plasma generating device provided in a first chamber and an ink-jet device provided in a second chamber, as is recited in amended claims 1, 9, and 19, Applicant respectfully submits Muehlberger, McMillan, Frey, and Ogawa, either alone or in combination, do not render claims 1, 9, or 19 obvious. Accordingly, Applicant respectfully requests this rejection be withdrawn.

Dependent claims 3-4, 10-12, 20-23, 29-31 and 33-60 depend from independent claims 1, 9, and 19, and are therefore allowable at least for the aforementioned reasons, and further for the additional features recited.

Conclusion

In view of the foregoing, it is submitted that the present application is in condition for allowance and a notice to that effect is respectfully requested. However, if any issue remains after considering this response, the Examiner is invited to call the undersigned to expedite the prosecution and work out any such issue by telephone.

Respectfully submitted,


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